Recent Progress of Stack Fixture Test at Pacific Northwest National Laboratory

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Generic Stack Test Fixture

Introduction:

To bridge the gap between "button" cells and industrial stacks, a generic stack fixture was developed at PNNL. The objective was to validate SOFC candidate materials, processing, and testing methods. In FY14 research was focused on:

1. Long-term validation and characterization of AISI441 interconnect with surface treatment

2. Effect of current density on the degradation of LSCF-based cells.

1. Long-term test with surface-modified AISI441

AISI441 is the leading candidate for metallic interconnect; however, Cr-oxide scale would continue to grow even under protective (Mn,Co)-spinel coating and can lead to spallation upon thermal cycling. To enhance scale adhesion mechanical interlocking was proposed and formed by metal grit blasting. In FY14 AISI441 was tested in a generic stack fixture with surface blasting of grit #40 and #80 at 800°C for 6000h.



Cr-oxide scale de-bonded after ageing 4000h at 800°C in air of the as-received AISI441 coated with (Mn,Co)-spinel.

Materials and Processing

- 1. Ce-(Mn,Co) spinel coating of surface-blasted **AISI441**
- 2. Aluminization of surface-blasted (#40, #80 grit) **AISI441**
- 3. AISI441 interconnect and window frame
- Refractory glass seal for WF/PEN at 930°C/2h
- 5. LSM20 or LSC20 and Ni paste + Ni mesh as contact
- 6. Final seal at 900-930°C/2h and tested at 800°C with fuel $H_2:N_2=1:1$ (3% H_2O) versus air at constant current mode
- 7. Impedance and IV sweep tests
- 8. Air side heat exchanger made of alumina (99%)

A commercial NiO-YSZ supported YSZ cell (5cm x 5cm) with LSM or LSCF cathode (16 cm²) and compressive mica perimeter seal

Cross-section of blasted AISI441







Long-term stability test at 800°C



EIS before and after~6300h stability test (grit #40)



EIS during thermal cycling after ~6300h stability test



Minute increase in ohmic resistance suggests no substantial de-bonding of Cr-oxide scale



Cell with #40 grit-blasted showed stable/low degradation





Impedance analysis



Post-test microstructure analysis

						C.	SM/YSZ	SZ act	ive ca ive an	thode ode		1 2 3 4				#91	n
Q	grit	#4(J		2	ØKV	<u>л</u> г, е		. O M m	1.	+5030	,1		ļ	JIII	#0	J
Area	0	Si	Cr	Mn	Ni	Sr	Zr	La	Area	0	Si	Cr	Mn	Ni	Sr	Zr	La
#1	60.67	0.23		19.04		4.68		15.64	#1	58.39			20.60		4.72		16.29
#2	68.38			9.15	0.28		16.19	7.01	#2	66.10			10.15			15.94	7.81
#3	46.88		0.04		31.32		21.97		#3	44.85				31.89		23.27	
#4	48.15		0.03		29.81		22.40		#4	45.80				31.17		23.03	
A.r.o.a	0	C:	6.1	N Are	NI:	6	7.	1.0	A.r.a.	0	C:	6.	Max	NE	6.4	7.	1.0
Area	50.20	51	Cr	10.90	INI	SI	Zſ	La 1C 07	Area	58.20	51	Cr	1VIN 20.25	INI	21	21	Ld
#1	59.30	0.40		19.80	0.22	4.64	15 92	7 50	#1	58.39			20.35	0.20	4.75	16 17	10.51
#2	45 48			5.55	33 30		21 35	7.55	#2	44 17			10.05	33 14		22 69	7.55
#4	47.93				29.88		22.52		#4	45.19				31.99		22.82	
Area	0	Si	Cr	Mn	Ni	Sr	Zr	La	Area	0	Si	Cr	Mn	Ni	Sr	Zr	La
#1	59.22	0.39		19.82		4.74		16.11	#1	57.73			20.81		4.99		16.48
#2	67.46			9.76	0.35		16.13	7.45	#2	66.21			10.01			16.01	7.76
#3	45.18		0.04		33.57		21.32		#3	42.36				35.42		22.22	
#4	47.79		0.02		29.99		22.46		#4	45.33				31.82		22.85	
																	-
Area	0	Si	Cr	Mn	Ni	Sr	Zr	La	Area	0	Si	Cr	Mn	Ni	Sr	Zr	La
#1	58.84	0.41		19.89		4.78		16.34	#1	57.88			20.51		5.20		16.41
#2	66.52			10.39		1.08	14.56	8.06	#2	67.59			9.36			15.72	7.34
#3	42.74				36.38		20.93		#3	43.60				33.86		22.54	
#4	46.70		0.01		31.00		22.61		#4	45.24				31.95		22.81	

No Cr detected in electrode for both #40 and #80 grits



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<u>2. Effect of current density on LSCF-based cell degradation</u></u>

Five LSCF-based cells were tested at 0, 125, 313, and 500 mA/cm² at 800°C





Summary and Conclusion

(A) Validation of surface treatment of AISI441 interconnect

1. AISI441 with surface blasting to enhance the Cr-oxide scale was validated at 800°C over 6000h. Results showed better cell performance for coarse grit #40 than finer grit #80. The cell performance of grit #40 was similar to the non-treated one.

2. EIS with various gases showed cathode side was rate limiting, and increase was primarily from ohmic part for both grits.

3. EIS of thermal cycling after 6000h test showed small increase in ohmic resistance, suggesting no Cr-oxide scale de-bonding. This is also consistent with SEM observation and EDS analysis of no Cr detected in electrode.

(B) Effect of current density on LSCF-based cell's performance 1. Five LSCF-based cells were tested at various current density (0-500 mA/cm²) and the results showed increased degradation with increasing current density, consistent with small "button" cells. 2. All cells showed parabolic behavior of ohmic resistance with constants 2-3 times greater than LSM-based cells. The mechanism

for this diffusion related process remains to be determined.

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